AMENDMENT TO THE SPECIFICATION:

Please amend the following specification paragraphs as indicated.

Page 7, lines 6-8: please delete the paragraph and substitute therefore with following paragraph:

The invention also encompasses masks repaired, enhance enhanced, and fabricated by these methods. The invention also provides methods of using scanning probe microscopy to repair and fabricate masks by additive repair and additive lithography, respectively.

Pages 7-8 beginning on line 30: please delete the entire paragraph and substitute therefore with following paragraph:

Examples include but are not limited to (xiv) the deposition of and/or filling with e.g. with with e.g. (a) a metal-rich material, such a metal or an alloy, and precursors thereof; (b) a carbon-rich material, such as graphite-like carbon (including fullerenes and carbon nanotubes and carbon nanotube derivatives), and diamond-like carbon; (c) colloidal particles, including metallic ones; and mixtures containing thereof, (d) one or more high-molecular-weight compound(s), including organic and inorganic polymers, with or without the addition of colloidal particles; (xv) the deposition of metal oxide, glasses, silicates and related materials; (xvi) the sequential deposition / filling materials according to xiv) and xv) (multilayer formation) with, optionally, control of the thickness and roughness of each layer, as well as the edge geometry.

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